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(54) Title: PROCESS AND APPARATUS FOR OBLIQUE BEAM REVOLUTION, FOR THE EFFECTIVE LASER STRIPPING OF SIDEWALLS

(57) Abstract

A process and apparatus for carrying out a substantially complete and accelerated removal of coating substance from the sidewalls of a surface to be stripped, comprising providing a laser beam incidence on the surface at an incidence angle α relative to the plane of the surface being treated, the said angle $\alpha > 0$ and periodically switching or gradually changing the azimuth of beam incidence plane.

